



Docket No.: 50351

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: P. Trefonas et al.

EXAMINER: Y. Clarke

SERIAL NO.: 09/219,468

GROUP: 1752

FILED: December 23, 1998

FOR: PHOTORESIST COMPOSITIONS PARTICULARLY SUITABLE FOR
SHORT WAVELENGTH IMAGING

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

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Sir:

AMENDMENT

Applicants file herewith a Request for Continued Examination. Please amend the application as follows.

IN THE CLAIMS

Please cancel without prejudice claims 1, 3-5, 7-11 and 13.

B¹ 12. (twice amended) A photoresist composition comprising a resin binder that comprises a polymer that contains pendant photoacid labile moieties and is substantially free of any aromatic groups, a photoacid generator and a non-aromatic amine compound that comprises a tertiary nitrogen alicyclic ring member.

B² 21. (amended) An article of manufacture comprising a microelectronic wafer or flat panel display substrate having coated thereon a layer of the photoresist composition of claim 12.